

IN THE CLAIMS:

Please substitute the following claims for the same-numbered claims in the application:

1-7 (Cancelled).

8. (Previously Presented) A cleaning apparatus used during the production of semiconductor wafers, said apparatus comprising:

a holder adapted to hold and rotate a semiconductor wafer;

an annular shield surrounding said semiconductor wafer such that said substrate is rotated within said shield; and

a dispenser positioned to dispense a cleaning fluid on said semiconductor wafer such that, when said semiconductor wafer is rotated within said shield and said cleaning fluid is dispensed, said cleaning fluid and foreign matter particles are ejected from said semiconductor wafer towards said shield,

wherein a surface of said shield facing said semiconductor wafer comprises a semi-permeable absorptive material that collects said cleaning fluid and said foreign matter particles to prevent splashing and

wherein said surface further comprises absorptive fins that provide air and fluid flow control such that said surface of said shield further prevents said cleaning fluid and said foreign matter particles from forming into a mist within said cleaning apparatus and being re-deposited back on said semiconductor wafer.

9-10. (Canceled).

11. (Currently Amended) The apparatus in claim 8, ~~all the limitations of which are incorporated herein by reference~~, wherein said semi-permeable material comprises one of an absorptive material, a screen material, and a perforated material.

12. (Currently Amended) The apparatus in claim 8, ~~all the limitations of which are incorporated herein by reference~~, wherein said semi-permeable material comprises a disposable material and is adapted to be periodically removed from said shield and replaced.

13. (Currently Amended) The apparatus in claim 8, ~~all the limitations of which are incorporated herein by reference~~, wherein said semi-permeable material comprises a permanent part of said shield.

14. (Currently Amended) The apparatus in claim 8, ~~all the limitations of which are incorporated herein by reference~~, wherein cleaning fluid ejected from the surface of the rotating semiconductor wafer is collected by and drains down said semi-permeable material.

15-20. (Canceled).

21. (Previously Presented) An apparatus comprising:
a holder adapted to hold and rotate a substrate;

an annular shield surrounding said substrate such that said substrate is rotated within said shield;

a dispenser positioned to dispense a fluid on said substrate such that, when said substrate is rotated within said shield and said fluid is dispensed, said fluid and foreign matter particles are ejected from said substrate towards said shield; and

a disposable liner on a surface of said shield facing said substrate,

wherein said disposable liner comprises a perforated material having perforations facing said substrate, said perforated material with said perforations collects said fluid and said foreign matter particles to prevent splashing, and

wherein said disposable liner further comprises absorptive fins that provide air and fluid flow control such that said disposable liner further prevents said fluid and said foreign matter particles from forming into a mist within said apparatus and being re-deposited back on said substrate.

22-25. (Canceled).

26. ((Currently Amended) The apparatus in claim 21, ~~all the limitations of which are incorporated herein by reference,~~ wherein said disposable liner is further adapted to drain said fluid and said foreign matter particles ejected from said substrate.